What is claimed is:

1. An apparatus for optically inspecting a sample, the apparatus comprising: an illumination source that generates a probe beam;

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a series of optical components that cause a portion of the probe beam to be reflected by a measurement area on the sample surface and subsequently transported to a detector, where the series of optical components includes at least one mirror, meeting the condition $TSE(D) \leq 2e^{-0.15D}$ where $TSE(D) = E_{mirror}(D)/E_{ideal}(D)$ where $E_{mirror}(D)$ is the encircled energy of the mirror measured as a function of the included diameter D and $E_{ideal}(D)$ is the encircled energy for an ideal diffraction-limited mirror of equal focal length and numerical aperture; and a processor for analyzing signals generated by the detector.

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An apparatus as recited in claim 1, wherein TSE(D) is a monotonically

15 decreasing function of D.

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decreasing function of D

3. An apparatus as recited in claim 1, wherein the mirror comprises: a glass substrate; and a reflective coating.

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4. An apparatus as recited in claim 1, wherein the mirror is formed using a glass master.

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An apparatus as recited in claim 1, wherein the mirror is formed by:
 diamond turning a substrate to a desired shape; and
 polishing the substrate to a surface roughness of approximately 10 Angstroms

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- 6. An apparatus as recited in claim 1, wherein the mirror is formed by: forming an aluminum substrate to a desired shape; and super-polishing the substrate to meet the condition $TSE(D) \le 2e^{-0.15D}$.
- 7. An apparatus for optically inspecting a sample, the apparatus comprising:
 an illumination source that generates a probe beam;
 a first series of optical components that direct the probe beam to be reflected by the sample;

a second series of optical components that gather the reflected probe beam

from a measurement area on the sample surface, where the series of optical
components includes at least one mirror, and where the series of optical components
transports at least 99% of the gathered illumination to a detector; and
a processor for analyzing signals generated by the detector.

- 8. An apparatus as recited in claim 7, wherein the mirror comprises:
 a glass substrate; and
 a reflective coating.
- 9. An apparatus as recited in claim 7, wherein the mirror is formed using a glass 20 master.
- 10. An apparatus as recited in claim 7, wherein the mirror is formed by: diamond turning a substrate to a desired shape; and polishing the substrate to meet the condition TSE(D) ≤ 2e^{-0.15D} where
 25 TSE(D) = E_{mirror}(D)/E_{ideal}(D) where E_{mirror}(D) is the encircled energy of the mirror measured as a function of the included diameter D and E_{ideal}(D) is the encircled energy for an ideal diffraction-limited mirror of equal focal length and numerical aperture.

- 11. An apparatus as recited in claim 10, wherein TSE(D) is a monotonically decreasing function of D.
- 12. An apparatus as recited in claim 7 wherein the mirror is formed by:
 forming an aluminum substrate to a desired shape; and
 super-polishing the substrate to meet the condition TSE(D) ≤ 2e^{-0.15D} where
 TSE(D) = E_{mirror}(D)/E_{ideal}(D) where E_{mirror}(D) is the encircled energy of the
 mirror measured as a function of the included diameter D and E_{ideal}(D) is the
 encircled energy for an ideal diffraction-limited mirror of equal focal length and
 numerical aperture.
 - 13. An apparatus as recited in claim 12, wherein TSE(D) is a monotonically decreasing function of D.
- 15 14. An apparatus as recited in claim 7 in which the measurement area is no larger than 50 microns.
 - 15. An apparatus for optically inspecting a sample, the apparatus comprising: an illumination source that generates a probe beam;

a series of optical components that cause a portion of the probe beam to be reflected by a measurement area on the sample surface and subsequently transported to a detector, where the series of optical components includes at least one mirror, and where at least 99% of the portion of the probe beam that is reflected by the measurement area reaches the detector; and

- a processor for analyzing signals generated by the detector.
- 16. An apparatus as recited in claim 15, wherein the mirror comprises:a glass substrate; anda reflective coating.

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- 17. An apparatus as recited in claim 15, wherein the mirror is formed using a glass master.
- 18. An apparatus as recited in claim 15, wherein the mirror is formed by:

 diamond turning a substrate to a desired shape; and

 polishing the substrate to meet the condition $TSE(D) \le 2e^{-0.15D}$ where $TSE(D) = E_{mirror}(D)/E_{ideal}(D)$ where $E_{mirror}(D)$ is the encircled energy of the mirror measured as a function of the included diameter D and $E_{ideal}(D)$ is the encircled energy for an ideal diffraction-limited mirror of equal focal length and numerical aperture.
 - 19. An apparatus as recited in claim 18, wherein TSE(D) is a monotonically decreasing function of D.
- 20. An apparatus as recited in claim 15, wherein the mirror is formed by: forming an aluminum substrate to a desired shape; and super-polishing the substrate to meet the condition TSE(D) ≤ 2e^{-0.15D} where TSE(D) = E_{mirror}(D)/E_{ideal}(D) where E_{mirror}(D) is the encircled energy of the mirror measured as a function of the included diameter D and E_{ideal}(D) is the encircled energy for an ideal diffraction-limited mirror of equal focal length and numerical aperture.
 - 21. An apparatus as recited in claim 20, wherein TSE(D) is a monotonically decreasing function of D.
 - 22. An apparatus as recited in claim 15 in which the measurement area is no larger than 50 microns.

23. A method for optically inspecting a sample, the method comprising: generating an optical probe beam;

using a series of optical components to cause a portion of the probe beam to be reflected by a measurement area on the sample surface and subsequently transported to a detector, where the series of optical components includes at least one mirror, meeting the condition $TSE(D) \le 2e^{-0.15D}$ where

 $TSE(D) = E_{mirror}(D)/E_{ideal}(D)$ where $E_{mirror}(D)$ is the encircled energy of the mirror measured as a function of the included diameter D and $E_{ideal}(D)$ is the encircled energy for an ideal diffraction-limited mirror of equal focal length and numerical aperture; and

analyzing signals generated by the detector.

24. An apparatus as recited in claim 23, wherein TSE(D) is a monotonically decreasing function of D.

25. A method as recited in claim 23, wherein the mirror comprises: a glass substrate; and a reflective coating.

- 26. A method as recited in claim 23, wherein the mirror is formed using a glass master.
 - 27. A method as recited in claim 23, wherein the mirror is formed by: diamond turning a substrate to a desired shape; and polishing the substrate to meet the condition $TSE(D) \le 2e^{-0.15D}$.
 - 28. A method as recited in claim 23, wherein the mirror is formed by: forming an aluminum substrate to a desired shape; and super-polishing the substrate to meet the condition $TSE(D) \le 2e^{-0.15D}$.

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29.	A method for optically inspecting a sample, the method comprising:
	generating an optical probe beam;
	using a first series of optical components to direct the probe beam to
reflected by the sample;	

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using a second series of optical components to gather the reflected probe beam from a measurement area on the sample surface, where the series of optical components includes at least one mirror, and where the series of optical components transports at least 99% of the gathered illumination to a detector; and analyzing signals generated by the detector.

30. A method as recited in claim 29, wherein the mirror comprises: a glass substrate; and a reflective coating.

31. A method as recited in claim 29, wherein the mirror is formed using a glass master.

- 32. A method as recited in claim 29, wherein the mirror is formed by: diamond turning a substrate to a desired shape; and polishing the substrate to a surface roughness meeting conditions meet the condition $TSE(D) \le 2e^{-0.15D}$ where $TSE(D) = E_{mirror}(D)/E_{ideal}(D)$ where $E_{mirror}(D)$ is the encircled energy of the mirror measured as a function of the included diameter D and $E_{ideal}(D)$ is the encircled energy for an ideal diffraction-limited mirror of equal focal length and numerical aperture.
- 33. An apparatus as recited in claim 32, wherein TSE(D) is a monotonically decreasing function of D.

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- 34. A method as recited in claim 23, wherein the mirror is formed by: forming an aluminum substrate to a desired shape; and super-polishing the substrate to meet the condition TSE(D) ≤ 2e^{-0.15D} where TSE(D) = E_{mirror}(D)/E_{ideal}(D) where E_{mirror}(D) is the encircled energy of the mirror measured as a function of the included diameter D and E_{ideal}(D) is the encircled energy for an ideal diffraction-limited mirror of equal focal length and numerical aperture.
- 35. An apparatus as recited in claim 34, wherein TSE(D) is a monotonically decreasing function of D.
 - 36. A method as recited in claim 32 in which the measurement area is no larger than 50 microns.
- 37. A method for optically inspecting a sample, the method comprising:
 generating an optical probe beam;
 using a series of optical components to cause a portion of the probe beam to
 be reflected by a measurement area on the sample surface and subsequently
 transported to a detector, where the series of optical components includes at least one
 mirror, and where at least 99% of the portion of the probe beam that is reflected by
 the measurement area reaches the detector; and
 analyzing signals generated by the detector.
 - 38. A method as recited in claim 37, wherein the mirror comprises:
 a glass substrate; and
 a reflective coating.
 - 39. A method as recited in claim 37, wherein the mirror is formed using a glass master.

- 40. A method as recited in claim 37, wherein the mirror is formed by: diamond turning a substrate to a desired shape; and polishing the substrate to meet the condition TSE(D) ≤ 2e^{-0.15D} where TSE(D) = E_{mirror}(D)/E_{ideal}(D) where E_{mirror}(D) is the encircled energy of the mirror measured as a function of the included diameter D and E_{ideal}(D) is the encircled energy for an ideal diffraction-limited mirror of equal focal length and numerical aperture.
- 41. An apparatus as recited in claim 40, wherein *TSE(D)* is a monotonically decreasing function of *D*.
- 42. A method as recited in claim 37, wherein the mirror is formed by: forming an aluminum substrate to a desired shape; and super-polishing the substrate to meet the condition TSE(D) ≤ 2e^{-0.15D} where
 15 TSE(D) = E_{mirror} (D)/E_{ideal} (D) where E_{mirror} (D) is the encircled energy of the mirror measured as a function of the included diameter D and E_{ideal} (D) is the encircled energy for an ideal diffraction-limited mirror of equal focal length and numerical aperture.
- 43. An apparatus as recited in claim 42, wherein TSE(D) is a monotonically decreasing function of D.
 - 44. A method as recited in claim 37 in which the measurement area is no larger than 50 microns.

- 45. A method for fabricating low-noise optical components for use in optical metrology systems, the method comprising:
 - creating a substrate that is similar in shape to the component to be produced; positioning a deformable layer over the substrate; and press forming the deformable layer using a master made from optical glass.
- 46. A method as recited in claim 45 in which the component is a mirror meeting the condition $TSE(D) \le 2e^{-0.15D}$ where $TSE(D) = E_{mirror}(D)/E_{ideal}(D)$ where $E_{mirror}(D)$ is the encircled energy of the mirror measured as a function of the included diameter D and $E_{ideal}(D)$ is the encircled energy for an ideal diffraction-limited mirror of equal focal length and numerical aperture.
- 47. A method as recited in claim 46 in which TSE(D) is a monotonically decreasing function of D.

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